L	Hits	Search Text	DB	Time stamp
Number -	51785	<pre>(mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)</pre>	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/06/03 09:04
_	25136	((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/06/03 09:05
-	26	"Ti") (((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:28
-	922	<pre>((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not (((mask\$3 or resist\$3 or photoresist) same ({etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/26 16:27
-	26	resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)) ((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/05/26 16:32
		<pre>(mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate)) and (mask\$3 or resist\$3 or photoresist) same (peel\$4 or pull\$4 or remov\$4 or lift\$3 adj off)</pre>		2003/05/26
-	854	<pre>((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4acrylate or \$4acrylate)) not ((((mask\$3 or resist\$3 or photoresist) same ((etch\$3 or chemical\$2 adj mil\$3 or deoxidiz\$3 or anodiz\$3) and metal)) and (mask\$3 or resist\$3 or photoresist) same (aluminum or "Al" or steel or titanium or "Ti")) and (mask\$3 or resist\$3 or photoresist) same (\$4urethane adj3 \$4acrylate or \$4urethane adj3 \$4acrylate o</pre>		16:32

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-	6	(((((mask\$3 or resist\$3 or photoresist)	USPAT;	2003/05/26
		<pre>same ((etch\$3 or chemical\$2 adj mil\$3 or</pre>	US-PGPUB;	16:34
		deoxidiz\$3 or anodiz\$3) and metal)) and	EPO; JPO;	
		(mask\$3 or resist\$3 or photoresist) same	IBM_TDB	
		(aluminum or "Al" or steel or titanium or	_	
		"Ti")) and (mask\$3 or resist\$3 or		
		photoresist) same (\$4urethane adj3		
		\$4acrylate or \$4urethane adj3		
		\$4acrylate)) and (mask\$3 or resist\$3 or		
		photoresist) same (peel\$4 or pull\$4 or		
		remov\$4 or lift\$3 adj off)) and (mask\$3		
		or resist\$3 or photoresist) same (scrib\$4		
		or cut\$4 or mark\$4 or scrap\$4)		
-	1560	(mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/06/03
		((deoxidiz\$3 or anodiz\$3) and metal)	US-PGPUB;	09:55
			EPO; JPO;	
			IBM TDB	
-	308	((mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/06/03
		((deoxidiz\$3 or anodiz\$3) and metal))	US-PGPUB;	09:10
		and (peel\$4 or remov\$4 or scrib\$4) adj3	EPO; JPO;	
		(mask\$3 or resist\$3 or photoresist)	IBM TDB	
-	495		USPAT;	2003/06/03
		((deoxidiz\$3 or anodiz\$3) and metal))	US-PGPUB;	09:11
		and (peel\$4 or remov\$4 or scrib\$4 or	EPO; JPO;	00.11
		pull\$4 or lift\$3 adj off) near3 (mask\$3	IBM TDB	
		or resist\$3 or photoresist)		
-	511		USPAT;	2003/06/03
		((deoxidiz\$3 or anodiz\$3) and metal))	US-PGPUB;	09:12
		and (peel\$4 or remov\$4 or scrib\$4 or	EPO; JPO;	
		pull\$4 or lift\$3 adj off or cut\$4 or	IBM TDB	
		scrap\$4) near3 (mask\$3 or resist\$3 or		
		photoresist)		
-	24	((mask\$3 or resist\$3 or photoresist) same	USPAT;	2003/06/03
		((deoxidiz\$3 or anodiz\$3) and metal))	US-PGPUB;	09:19
		and (peel\$4 or remov\$4 or scrib\$4 or	EPO; JPO;	
		pull\$4 or lift\$3 adj off or cut\$4 or	IBM TDB	
		scrap\$4) near3 (mask\$3 or resist\$3 or	-	
		photoresist) same (seal\$3)		1
-	1	(maskant or mask) and line adj sealant	USPAT;	2003/06/03
		<pre>same ((deoxidiz\$3 or anodiz\$3) and metal)</pre>	US-PGPUB;	09:57
			EPO; JPO;] [
			IBM_TDB	
-	0	(maskant or mask) and line adj sealer	USPAT;	2003/06/03
		<pre>same ((deoxidiz\$3 or anodiz\$3) and metal)</pre>	US-PGPUB;	10:29
			EPO; JPO;	
			IBM_TDB	
-	92	(216/42,44,47,48,101-102 or	USPAT;	2003/06/03
		430/320,323-324 or	US-PGPUB;	19:08
		205/122,135,153,188,320,324).ccls. and	EPO; JPO;	
		seal\$3 same mask\$3	IBM_TDB	
-	145	(IRGACURE adj "1700") or (IRACURE adj	USPAT;	2003/06/04
		"1700")	US-PGPUB;	18:11
			EPO; JPO;	
			IBM_TDB	
-	23	((IRGACURE adj "1700") or (IRACURE adj	USPAT;	2003/06/04
		"1700")) and (wax or (synergist and	US-PGPUB;	18:12
		triethanolamine))	EPO; JPO;	
			IBM_TDB	